The heating means may include a heating chamber 14 and a plurality of heat exchange units 15 placed in line from an upper to a lower part of the heating chamber 14, forming two rows. The heat exchange units may comprise Inconel® tubes that are placed in double lines, which run from the upper part to the lower part of the heating chamber 14, in order to supply heat evenly to the exhaust gas. The temperature can be adjusted by adding or reducing heat to the (or the number of) Inconel® tubes. A ceramic heater 15a that generates heat with electricity is placed in the inside of the heat exchange unit 15. An insulator such as quartz 15b, which is a heat retention material, is placed between the heater 15a and heat exchange unit outer surface.

D1

Please replace pg. 7, lines 4-13, of the amended Specification (Attachment A of the Response to the Office Action mailed October 4, 2000) with the amended paragraph below. A "marked-up" version of each amendment is included in **Attachment A**.

A controller (not illustrated in the drawings) controls the amount of heat by regulating the flow of electricity. The heaters 15a are divided into two sets and two different sets of electricity supply means are connected to the heaters, respectively. When electricity is discontinued in one set of the heaters, twice the amount of electricity is then supplied to the other set of heaters to generate twice the amount of heat within the other set of heaters. The heater 15a is connected to an electric wire (i.e., electric power conductor, not illustrated in the drawings) with a clamp made of a stainless material, and when the high temperature is transmitted, oxidation or thermal variation may occur upon the clamp which can result in breakage of a wire. In order to prevent the thermal variation or the oxidation occurring in the clamp, a nitrogen nozzle 16 is attached to supply nitrogen across the clamp, to cool the clamp and prevent oxidation thereon.

D2

Please replace pg. 8, lines 4-15, of the amended Specification (Attachment A of the Response to the Office Action mailed October 4, 2000) with the amended paragraph below. A "marked-up" version of each amendment is included in **Attachment A**.

After passing through the combustion chamber 10 and the explosive and flammable elements are removed, the gas flows into the wetting chamber 30, which is placed below the combustion chamber 10 forming a single unit. The wetting chamber 30 comprises a case having a central part that is formed with a plurality of partitions 31a configured to form a passage where the gas enters from the combustion chamber 10, and a lower part containing water. A plurality of absorbers installed in the gas passage formed by the partitions 31a of the case 31 are then used to dissolve the water soluble harmful elements

D3

contained in the gas as the gas flows in an up and down direction along the passage and passes through a plurality of absorbers 32 alternatively. A shower nozzle 33 installed above each absorber sprays water to the corresponding absorber, and an exhaust pipe 50 is used to let out the treated gas removed of the harmful elements to the atmosphere.

Please replace pg. 8, lines 17-24, of the amended Specification (Attachment A of the Response to the Office Action mailed October 4, 2000) with the amended paragraph below. A "marked-up" version of each amendment is included in **Attachment A**.

The bottom of the case 31 is formed in v-shape for collecting byproduct particles. A drain 41 and a water nozzle 42 are installed at the lateral side of the v-shape bottom. A sensor 34 is placed above the drain 41 to monitor the water level. An output signal from the sensor 34 initiates the water nozzle 42 to inject water to push the water-entrained particles, or sludge, out to the drain 41 when the sludge gathered at the bottom of the case 31 reaches a certain amount and causes the water level to rise. A transparent plate 44 is hinged on one side of the case so that the water level could be checked from outside in case the sensor malfunctions.

Please replace pg. 9, lines 16-24, of the amended Specification (Attachment A of the Response to the Office Action mailed October 4, 2000) with the amended paragraph below. A "marked-up" version of each amendment is included in **Attachment A**.

Figs. 6 and 7 are hereby used to illustrate various methods for treating the gas produced during the semiconductor manufacturing process with the gas scrubber. The gas comprising hydrogen and other noxious elements that were not treated in the CVD furnace is fed into the combustion chamber 10 through the gas intake 11, 11'. A number of the gas intakes 11, 11' used is preferably based on the maximum capacity of the gas scrubber. For example, if the maximum capacity of the gas scrubber is 2000 slm (i.e., standard liters per minute), then four exhaust gas service pipes connected to four devices that exhaust 500 slm of exhaust gas should be formed. The modular addition of exhaust gas pipes and associated combustion chambers is thereby contemplated.

Please replace pg. 11, lines 20-23, of the amended Specification (Attachment A of the Response to the Office Action mailed October 4, 2000) with the amended paragraph below. A "marked-up" version of each amendment is included in **Attachment A**.